



## Q. Metrology, Inspection, Analysis, and Yield Enhancement 분과

2021년 1월 29일(금), 14:45-16:15 / 채널 A

### [FA4-Q] Nanoanalysis and Characterization

좌장: 정용우 박사 (SK하이닉스), 조용재 박사 (KRISS)

<p><b>FA4-Q-1</b> 14:45-15:15</p>	<p><b>[초청]</b> 반도체 공정 플라즈마 정밀 측정기술 및 소재/부품/장비 정량화 평가기술 이효창, 김정형 한국표준과학연구원</p>
<p><b>FA4-Q-2</b> 15:15-15:30</p>	<p><b>Semiconductor Analysis Techniques at NNFC</b> Jun-Mo Yang Nano-Convergence Technology Division, NNFC</p>
<p><b>FA4-Q-3</b> 15:30-15:45</p>	<p><b>Development of Optical Characterization Equipment for Si Wafer Monitoring in Ion Implantation Process</b> YoungMin Park<sup>1</sup>, HyunDon Jung<sup>1</sup>, DongHan Kim<sup>1</sup>, JungMin Kim<sup>1</sup>, YongHee Jeon<sup>1</sup>, GyuHyeong Cho<sup>1</sup>, Sung-Jin Chang<sup>2</sup>, Woo Sik Soun<sup>2</sup>, Chil Seong Jeong<sup>2</sup>, Jong-Bum You<sup>2</sup>, and Jin Su Kim<sup>2</sup> <sup>1</sup>Etamax Co., Ltd, <sup>2</sup>National Nanofab Center</p>
<p><b>FA4-Q-4</b> 15:45-16:00</p>	<p><b>Analysis of Ferroelectric Modulation Structure in MOS structure</b> Min Baik<sup>1</sup>, Deok Joon Eom<sup>2</sup>, Jonghoon Kim<sup>1</sup>, Hyeon-Sik Kim<sup>1</sup>, Kwang-Sik Jeong<sup>1</sup>, Jin Dong Song<sup>3</sup>, Hyoungsub Kim<sup>2</sup>, and Mann-Ho Cho<sup>1</sup> <sup>1</sup>Department of Physics, Yonsei University, <sup>2</sup>School of Advanced Materials Science and Engineering, Sungkyunkwan University, <sup>3</sup>Center of Opto-electronic Materials, KIST</p>
<p><b>FA4-Q-5</b> 16:00-16:15</p>	<p><b>지능형 반도체의 고속 동작 특성 평가용 테스트 패턴</b> 최현웅, 김성현, 송기우, 이희덕 충남대학교 전자공학과</p>

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